



Attorney Docket: 081468-63063  
Client Reference: P-1942.063-US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:

Confirmation Number: 8455

HOFFMAN ET AL.

Application No.: 10/759,699

Group Art Unit: 2873

Filed: January 19, 2004

Examiner: HASAN, MOHAMMED A.

Title: CORRECTION OF BIREFRINGENCE IN CUBIC CRYSTALLINE OPTICAL SYSTEMS

February 16, 2005

REQUEST FOR RETURN OF INITIALED PTO-1449

Mail Stop ISSUE FEE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

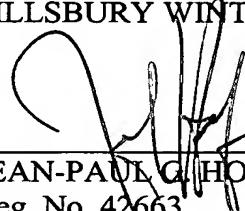
Sir:

The Applicants respectfully request that a copy of the PTO-1449, filed November 22, 2004, be returned with the Examiner's initials in the left column per MPEP § 609. A copy of the PTO-1449, as originally filed, is enclosed.

Respectfully submitted,

PILLSBURY WINTHROP LLP

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Atty. Dkt. No.	M#	Client Ref.
	310701	P-1943.063-US
Applicant: HOFFMAN et al.		
Appln. No.: 10/759,699		
Filing Date: January 19, 2004		
Examiner: M. HASAN		Group Art Unit: 2873

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Date: November 22, 2004

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**U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AR	5,410,375	04/1995	Fiala			
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CR	6,411,384	06/2002	Sakuma et al.			
DR	6,417,974	07/2002	Schuster			
ER	6,583,931	06/2003	Hiraiwa et al.			
FR	6,672,109	01/2004	Hiraiwa			
GR	6,683,729	01/2004	Schuster			
HR	6,697,199	02/2004	Gerhard et al.			
IR	6,728,043	04/2004	Gruner et al.			
JR	6,775,063	08/2004	Shiraishi			
KR	2002/0085176	07/2002	Hiraiwa et al.			
LR	2002/0149855	10/2002	Schuster			
MR	2002/0186355	12/2002	Omura			
NR	2003/0000453	01/2003	Unno et al.			
OR	2003/0007253	01/2003	Schuster et al.			
PR	2003/0012724	01/2003	Burnett et al.			
QR	2003/0063393	04/2003	Omura			

**FOREIGN PATENT DOCUMENTS**

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
RR	DE 101 23 725	11/2002	Germany	Wagner et al.			X	
SR	DE 101 23 727	11/2002	Germany	Brunotte et al.			X	
TR	DE 101 25 487	01/2003	Germany	Brunotte et al.			X	
UR	DE 101 27 320	12/2002	Germany	Brunotte et al.		X		
VR	DE 102 10 782	10/2003	Germany	Krämer et al.		X		
WR	2002-302628	10/2002	Japan	Mitsuhiko et al.		X		
XR	2003-050349	02/2003	Japan	Naomasa et al.		X		
YR								
ZR								
AAR								

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

BBR

Examiner

Date Considered:

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)  
 To: U.S. Department of Commerce  
 (PW FORM PAT-1449)  
 Patent and Trademark Office

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		310701 P-1943.063-US
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#### INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)
CCR	2003/0086157	05/2003	McGuire, Jr.
DDR	2003/0086171	05/2003	McGuire
EER	2003/0089299	05/2003	Obara et al.
FFR	2003/0091934	05/2003	Allan et al.
GGR	2003/0112501	06/2003	Sakuma
HHR	2003/0128349	07/2003	Unno
IIR	2003/0147061	08/2003	Omura
JJR	2003/0197946	10/2003	Omura
KKR	2003/0234981	12/2003	Hoffman et al.
LLR	2004/0001244	01/2004	Hoffman et al.
MMR	2004/0004757	01/2004	Schuster
NNR	2004/0004771	01/2004	Omura
OOR	2004/0005266	01/2004	Sakuma et al.
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QQR	2004/0036971	02/2004	McGuire, Jr.
RRR	2004/0036985	02/2004	McGuire, Jr.
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TTR	2004/0136084	07/2004	Unno

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UUR	WO 01/01182	01/2001	WIPO	Meda et al.			
VVR	WO 02/093257	11/2002	WIPO	Brunotte et al.		X	
WW	WO 03/003429	01/2003	WIPO	Omura et al.		X	
XXR	WO 03/007046	01/2003	WIPO	Yamaguchi		X	
YYR	WO 03/046634	06/2003	WIPO	Omura et al.		X	
ZZR	WO 03/077011	09/2003	WIPO	Fiolka et al.			
AAA	WO 03/077007	09/2003	WIPO	Goehnermeier et al.		X	
BBB	WO 03/088330	10/2003	WIPO	Yamaguchi		X	
CCC	WO 04/008254	01/2004	WIPO	Yamada			
DDD							

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AR						

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					Enclosed	No	Enclose	No
BR								

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CR	Burnett et al., "Intrinsic Birefringence in 157 nm Materials," <i>National Institute of Standards and Technology</i> , SEMATECH Calcium Fluoride Birefringence Workshop, July 18, 2001, Slides.			
DR	Burnett et al., "Intrinsic Birefringence in Calcium Fluoride and Barium Fluoride," <i>Rapid Communications</i> , Physical Review B, Vol. 64, November 29, 2001, pp. 241102-1 - 4.			
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FR	Chiba et al., "New Generation Projection Optics for ArF Lithography," <i>Optical Microlithography XV</i> , Proceedings of SPIE, Vol. 4691, 2002, pp. 679-686.			
GR	Matsumoto et al., "Analysis of Imaging Performance Degradation," <i>Optical Microlithography XVI</i> , Proceedings of SPIE, Vol. 5040, 2003, pp. 131-138.			
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PR	Nogawa et al., "System Design of a 157nm Scanner," <i>Canon Inc.</i>			

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QR						

**FOREIGN PATENT DOCUMENTS**

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
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RR								

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SR	Unno et al., "Analyses of Imaging Performance Degradation Caused by Birefringence Residual in Lens Materials," <i>Optical Microlithography XIV</i> , Proceedings of SPIE, Vol. 4346, 2001, pp. 1306-1317.			
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DDR	Wang, "157 nm Birefringence Measurement System Using PEM Technology," <i>Hinds Instruments</i> , Slides.			
EER	Ware, "Pushing ArF to the Limits!," <i>Canon USA, DNS Lithography Breakfast Forum at SEMICON West 2003</i> , July 2003, Slides.			

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					Enclose	No

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HHR	Webb, Intrinsic Birefringence Workshop, Coming, Corning Tropel, July 18, 2001, Slides.		
IIR	Zeiss et al., "Intrinsic Birefringence in CaF <sub>2</sub> ," Zeiss, CaF <sub>2</sub> Birefringence Workshop, Slides.		
JJR	"Business and Technology Update," Canon Europa N.V., Amstelveen, Slides.		
KKR	Memorandum from C. Van Peski to Exposure Tool Manufacturers and Lens Designers, Regarding Birefringence of Calcium Fluoride, May 7, 2001, XP-002218848.		
LLR	Memorandum from C. Van Peski to PAG Members, Regarding Birefringence of Calcium Fluoride, May 7, 2001.		
MMR			
NNR			
OOR			
PPR			
QQR			
RRR			
SSR			
TTR			
UUR			
VVR			
WWI			

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